Walter E Henderson

List of Publications by Year in descending order

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840776 752698 31 407 11 20 citations h-index g-index papers 31 31 31 568 docs citations times ranked citing authors all docs

#	Article	IF	CITATIONS
1	InN: A material with photovoltaic promise and challenges. Journal of Crystal Growth, 2006, 288, 218-224.	1.5	82
2	Transient atomic behavior and surface kinetics of GaN. Journal of Applied Physics, 2009, 106, .	2.5	41
3	III-nitride integration on ferroelectric materials of lithium niobate by molecular beam epitaxy. Applied Physics Letters, 2005, 87, 171107.	3.3	34
4	Molecular beam epitaxy of complex metal-oxides: Where have we come, where are we going, and how are we going to get there?. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2005, 23, 1272.	1.6	32
5	Spatially resolved 3D metabolomic profiling in tissues. Science Advances, 2021, 7, .	10.3	29
6	Extremely high hole concentrations in câ€plane GaN. Physica Status Solidi C: Current Topics in Solid State Physics, 2009, 6, S788.	0.8	27
7	Strain relaxation via formation of cracks in compositionally modulated two-dimensional semiconductor alloys. Npj 2D Materials and Applications, 2018, 2, .	7.9	23
8	Halide based MBE of crystalline metals and oxides. Physica Status Solidi C: Current Topics in Solid State Physics, 2012, 9, 155-160.	0.8	20
9	Mg doped GaN using a valved, thermally energetic source: enhanced incorporation, and control. Journal of Crystal Growth, 2005, 279, 26-30.	1.5	18
10	A versatile metal-halide vapor chemistry for the epitaxial growth of metallic, insulating and semiconducting films. Journal of Crystal Growth, 2011, 324, 134-141.	1.5	17
11	Growth of InN on Ge substrate by molecular beam epitaxy. Journal of Crystal Growth, 2005, 279, 311-315.	1.5	14
12	Complementary oxide memristor technology facilitating both inhibitory and excitatory synapses for potential neuromorphic computing applications. , 2009, , .		12
13	III-Nitride Growth on Lithium Niobate: A New Substrate Material for Polarity Engineering in III-Nitride Heteroepitaxy. Materials Research Society Symposia Proceedings, 2002, 743, L1.4.1.	0.1	11
14	Influence of growth conditions and surface reaction byproducts on GaN grown via metal organic molecular beam epitaxy: Toward an understanding of surface reaction chemistry. Journal of Electronic Materials, 2006, 35, 562-567.	2.2	7
15	Growth and characterization of AlxGa1â^*xN via NH3-based metal-organic molecular beam epitaxy. Journal of Crystal Growth, 2009, 311, 1328-1332.	1.5	6
16	A mechanistic study of the interaction of water-soluble borate glass with apatite-bound heterocyclic nitrogen-containing bisphosphonates. Acta Biomaterialia, 2016, 31, 339-347.	8.3	5
17	Mg Doped GaN Using a Valved, Thermally Energetic Source: Enhanced Incorporation, Control and Quantitative Optimization. Materials Research Society Symposia Proceedings, 2003, 798, 719.	0.1	4
18	Mixed alkyl exchange and exploitable surface interactions in InGaN by NH3-based metal organic molecular beam epitaxy. Journal of Crystal Growth, 2008, 310, 5297-5302.	1.5	4

#	Article	IF	Citations
19	Fractal Electrode Formation in Metal–Insulator Composites Near the Percolation Threshold. IEEE Nanotechnology Magazine, 2013, 12, 725-733.	2.0	4
20	ALD TiOxas a top-gate dielectric and passivation layer for InGaZnO115ISFETs. Semiconductor Science and Technology, 2017, 32, 114004.	2.0	4
21	Molecular Beam Epitaxy of Lithium Niobate Multifunctional Materials Using a Chloride Refractory Metal Chemistry. ECS Transactions, 2006, 2, 103-114.	0.5	3
22	Growth kinetics of AlxGa1–xN grown via ammonia-based metal-organic molecular beam epitaxy. Journal of Crystal Growth, 2010, 312, 209-212.	1.5	3
23	Molecular Beam Epitaxial Growth of AlN/GaN Multiple Quantum Wells. Materials Research Society Symposia Proceedings, 2002, 743, L6.2.1.	0.1	2
24	In situ Auger probe enabling epitaxy composition control of alloys by elemental surface analysis. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2013, 31, 03C126.	1.2	2
25	An investigation of the effects of radiation exposure on stability constraints in epitaxial SiGe strained layers. Solid-State Electronics, 2006, 50, 1194-1200.	1.4	1
26	Investigation into the use of molecular hydrogen on the growth of gallium nitride via metal-organic molecular beam epitaxy. Physica Status Solidi C: Current Topics in Solid State Physics, 2008, 5, 1723-1725.	0.8	1
27	Impact of Microstructure on Dielectric Nanocomposites With High- <italic>k</italic> Interfacial Layers. IEEE Nanotechnology Magazine, 2015, 14, 717-725.	2.0	1
28	Reclamation of a molecular beam epitaxy system and conversion for oxide epitaxy. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2008, 26, 1501-1506.	2.1	0
29	High-Temperature Growth of GaN and Al x Ga1â^'x N via Ammonia-Based Metalorganic Molecular-Beam Epitaxy. Journal of Electronic Materials, 2010, 39, 473-477.	2.2	O
30	Using a university characterization facility to educate the public about microscopes: light microscopes to SEM. , 2015, , .		0
31	Characterization and Simulation of Permittivity Enhancements of Si <inf>O2</inf> /Si <inf>3</inf> N <inf>4</inf> Nanolaminate Layers., 2018,		O